Amendments of the Claims

The following list of claims replaces all previous version(s) of claims.

- 1 -7 Canceled
- 8. (Currently amended) A method of forming a patterned material structure on a substrate, said method comprising:
- (A) providing a substrate with a layer of said material wherein said material is chromiumcontaining metal composition,
- (B) applying a resist composition to said substrate to form a resist layer on said substrate, said resist composition comprising
 - a) an imaging polymer,
 - b) acid-labile moieties,

exposed portions of said resist, and

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- c) a radiation-sensitive acid generator, and
- d) a base additive component, wherein said base additive component comprises:
- (i) a room temperature solid base selected from the group consisting of aromatic amines and imidazoles N. N-dimethylaminopyridine, and
- (ii) a liquid low vapor pressure base consisting of triethanolamine, wherein a mole ratio of said low vapor pressure base to said solid base is in the range of 0.15 to 0.5,
- (C) patternwise exposing said substrate to electron beam radiation whereby acid is generated by radiation-sensitive acid generator in exposed regions of said resist layer,
 (D) forming a patterned resist structure having a vertical profile by removing radiation-

(E) transferring resist structure pattern to said material layer by removing portions of said material layer through spaces in said resist structure pattern.

Canceled.

10. (Previously presented) The method of claim 8 wherein said acid-labile protecting group is a moiety selected from the group consisting of ketals, and orthoesters.

11. (Previously presented) The method of claim 8 wherein said transfer of step (E) comprises reactive ion etching.

12. (Original) The method of claim 8 wherein at least one intermediate layer is provided between said material layer and said resist layer, and step (E) comprises etching through said intermediate layer.

 (Original) The method of claim 8 wherein said resist is thermally treated between steps (C) and (D).

14 - 19. Canceled.